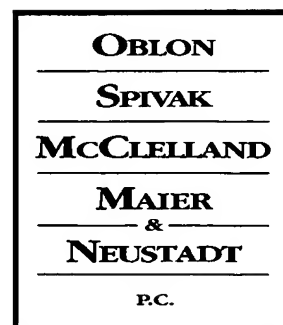




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Docket No: 240579US6 YA

COMMISSIONER FOR PATENTS
ALEXANDRIA, VIRGINIA 22313

RE: Application Serial No.: 10/647,534
Applicants: Anthony DIP et al.
Filing Date: August 26, 2003
For: MULTIPLE GROW-ETCH CYCLIC SURFACE
TREATMENT FOR SUBSTRATE PREPARATION
Group Art Unit: 2823
Examiner: MALDONADO, JULIO J.

ATTORNEYS AT LAW

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SIR:

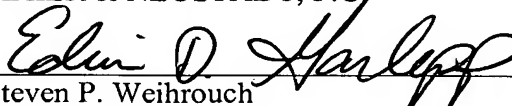
Attached hereto for filing are the following papers:

RESPONSE TO RESTRICTION REQUIREMENT

Our check in the amount of \$0.00 is attached covering any required fees. In the event any variance exists between the amount enclosed and the Patent Office charges for filing the above-noted documents, including any fees required under 37 C.F.R. 1.136 for any necessary Extension of Time to make the filing of the attached documents timely, please charge or credit the difference to our Deposit Account No. 15-0030. Further, if these papers are not considered timely filed, then a petition is hereby made under 37 C.F.R. 1.136 for the necessary extension of time. A duplicate copy of this sheet is enclosed.

Respectfully submitted,

OBLON, SPIVAK, McCLELLAND,
MAIER & NEUSTADT, P.C.


Steven P. Weihrouch

Registration No. 32,829

Customer Number

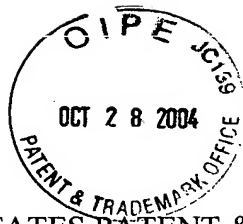
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DOCKET NO: 240579US6 YA



IN THE UNITED STATES PATENT & TRADEMARK OFFICE

IN RE APPLICATION OF :
ANTHONY DIP ET AL. : EXAMINER: MALDONADO, JULIO J.
SERIAL NO: 10/647,534 :
FILED: AUGUST 26, 2003 : GROUP ART UNIT: 2823
FOR: MULTIPLE GROW-ETCH CYCLIC SURFACE TREATMENT FOR SUBSTRATE
PREPARATION

RESPONSE TO RESTRICTION REQUIREMENT

COMMISSIONER FOR PATENTS
ALEXANDRIA, VA 22313-1450

SIR:

In response to the Restriction Requirement dated September 28, 2004, Applicants provisionally elect with traverse Group I, Claims 1-12, drawn to a method of manufacturing a semiconductor device.

MPEP § 803 states:

MPEP § 803

. . . If the search and examination of an entire application can be made without serious burden, the Examiner must examine it on the merits, even though it includes claims to distinct or independent inventions.

However, the outstanding Restriction Requirement has not established that an undue burden would exist if the Restriction Requirement was not issued and all the claims were examined together. Moreover, the claims of the present invention would appear to be part of an overlapping search area. Accordingly, Applicants respectfully traverse the outstanding Restriction Requirement on the grounds that a search and examination of the entire application would not place a *serious* burden on the Examiner.

Application Serial Number: 10,/647,534

In response to Restriction Requirement dated September 28, 2004

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Accordingly, it is respectfully requested that the requirement to elect a single group be withdrawn, and that a full examination on the merits of Claims 1-16 be conducted.

Respectfully submitted,

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SPW:EDG:ldm

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